

Welcome to Resist TWG Meeting

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Agenda



Time	Title	Presenter
8:30 AM – 8:40 AM	Welcome and Introductions	<i>Stefan. Wurm, SUNY Poly SEMATECH / GF</i>
8:40 AM – 8:50 AM	Resist performance review and requirements discussion	<i>Yu-Jen Fan, SUNY Poly SEMATECH</i>
8:50 AM – 9:10 AM	Soft Xray Absorption Spectroscopy using SR for EUV Resist Chemical Reaction Analysis	<i>Takeo Watanabe, University of Hyogo</i>
9:10 AM – 9:30 AM	Measurements of PAG reaction cross sections to low energy electrons	<i>Gregory Denbeaux, SUNY Poly Institute</i>
9:30 AM – 9:50 AM	Progress of DDRM for EUV lithography	<i>Rikimaru Sakamoto, Nissan Chemical</i>
9:50 AM – 10:00 AM	Resist development update at Inpria	<i>Andrew Grenville, Inpria</i>
10:00 AM – 10:20 AM	Alternative material status at imec	<i>Danilo De Simone, imec</i>
10:20 AM – 10:30 AM	LBNL update	<i>Patrick Naulleau, LBNL</i>
10:30 AM – 10:50 AM	Coffee break / Social network	
10:50 AM – 11:10 AM	Outgassing of CAR and alternative resists: The way forward	<i>Gijsbert Rispens, ASML</i>
11:10 AM – 11:30 AM	Update of resist outgas testing at EIDEC	<i>Eishi Shiobara, EIDEC</i>
11:30 AM – 11:50 AM	A plan to measure EUV resist contamination in the presence of hydrogen	<i>Gregory Denbeaux for NIST</i>
11:50 AM – 12:00 PM	Summary	<i>Yu-Jen Fan, SUNY Poly SEMATECH</i>
12:00 PM – 13:00 PM	Lunch	

